

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	2	(("6,665,577") or ("20040071888") or ("6,615,142")).PN.	US- PGPUB; USPAT; USOCR	OR	OFF	2006/06/30 17:01
S2	3	(("6,665,577") or ("20040071888") or ("6,615,142")).PN.	US- PGPUB; USPAT; USOCR	OR	OFF	2006/06/30 17:02
S3	2889	(702/57,58,109,110,117,118,119).CCLS.	US- PGPUB; USPAT; USOCR	OR	OFF	2008/07/04 15:57
S4	438	(324/718,716).CCLS.	US- PGPUB; USPAT; USOCR	OR	OFF	2008/07/04 15:57
S6	750	(438/18).CCLS.	US- PGPUB; USPAT; USOCR	OR	OFF	2008/07/04 15:57
S7	946	(700/109,110).CCLS.	US- PGPUB; USPAT; USOCR	OR	OFF	2008/07/04 15:58

S8	18	(calculat\$3 manipulat\$3) with (semiconductor\$1 wafer\$1 structure\$1 wafer\$1) with (goodness with fit\$3)	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 15:58
S9	7540	(wafer\$1 chuck\$1 workpiece\$1) with (detect\$3 monitor\$3) with (defect\$3 anomal\$3 error\$1 fault\$3 fail\$3)	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 15:59
S10	163	test\$3 with condition\$3 with (temperatur\$3 with intensity)	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 15:59
S11	0	(curve near fit\$3) and (process\$3 with (control \$3 monitor\$3)) and (detect\$3 with defect\$1) and ((goodness nearl (fit\$4 measur\$3)) (coefficient\$1 near correlation\$1)) and (sheet\$1 near (resistance resistivity))	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:00
S12	0	((wafer\$1 near defect\$1)with (screen\$3 monitor \$3) and (statistic\$3 with process\$3 with control \$3) and (ATE with testers)	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:01
S13	0	(wafer\$1 with tester\$1) same (process\$3 with evaluat\$3) same (statistic\$3 with (fit\$3 best\$1 fit \$3))	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:01
S14	7	("4031370" "4905170").PN. OR ("5796983").URPN.	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:01

S15	2	(\$3 \$4 \$6 \$7) and \$8	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:02
S16	18	("4855253" "5717490" "5739909" "5835225" "6015718" "6072191" "6146910" "6263255" "6297880" "6298470" "6309900" "6347291" "6484064").PN. OR ("6743646").URPN.	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:02
S17	8	(wafer\$1 with tester\$1) same (process\$3 with evaluat\$3) same screen\$3 and (control\$3 with process\$3)	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:02
S18	48	(curve near fit\$3) and (process\$3 with (control \$3 monitor\$3)) and (detect\$3 with defect\$1) and ((goodness near1 (fit\$4 measur\$3)) (coefficient\$1 near correlation\$1)) and (sheet\$1 near (resistance resistivity))	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:03
S19	0	(wafer\$1 with tester\$1) same (process\$3 with evaluat\$3) same (statistic\$3 with (fit\$3 GOF best\$1 fit\$3))	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:04
S20	0	((manipulat\$5 calculat\$5 form\$3) with (goodness near1 (fit\$3 measur\$4 statistical\$3))) and ((semiconductor\$1 wafer\$1) with (form\$3 near process\$3)) and (independent with variable \$1)	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:04
S21	19	(test\$3 with structur\$3) and (wafer\$1 chuck\$1 with workpiece\$1) and (defect\$3 with monitor \$3) and ((goodness with fit\$3) (curve\$1 with fit \$3))	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:05

S22	1	((structure with test\$3 with parameter\$1) and ((measur\$3 with monitor\$3) with value\$1) and (goodness with fit\$3 with differenc\$3) and (value\$1 with differenc\$3))	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:06
S23	5	((histor\$3 with value\$1) same curve\$1) and (goodness with fit\$3) and ((control\$3 with limit\$3) (threshold with value\$1) (referenc\$3 with value\$1)))	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:06
S24	0	(S14 S6 S7) and S22	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:07
S25	7	(S14 S6 S7) and S14	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:07
S26	0	S25 and S16	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:07
S27	0	S25 and S10	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:07
S28	2	(fit\$3 with curve\$1 with value\$1) and ((wafer\$1 chuck\$1 workpiece\$1 substrat\$3 structure\$1) with monitor\$3 with defect\$3)	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:08

S29	0	(fit\$3 with curve\$1 with value\$1) and ((wafer\$1 chuck\$1 workpiece\$1 substrat\$3 structure\$1) with monitor\$3 with defect\$3) and (compar\$3 with ((referenc\$3 threshold) with value\$1))	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:08
S30	204	(wafer\$1 chuck\$1 workpiece\$1) with (detect\$3 monitor\$3) with (defect\$3 anomal\$3 error\$1 fault\$3 fail\$3) and (fit\$3 with (curv\$3 graph\$3 plot\$3))	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:08
S31	2	("5345392" "6968291").PN. OR ("7081823").URPN.	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:09
S32	30	("4933887" "4944590" "4950990" "4965451" "5020920" "5047713" "5099441").PN. OR ("5667300").URPN.	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:09
S34	0	(((manipulat\$5 calculat\$5 form\$3) with (goodness near1 (fit\$3 measur\$4 statistical \$3))) and ((semiconductor\$1 wafer\$1) with (form\$3 near process\$3))) and (independent with variable\$1)).clm.	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:11
S35	0	S34 and (S3 S4 S6 S7)	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:11
S36	1	(monitor\$3 with (process\$3 near stability)) and (fit\$3 with value\$1) and (linear\$3 with regression \$3) and (coefficient\$1 near (relat\$3 correlat\$3))	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:11

S37	1	(monitor\$3 with (process\$3 near stability)) and (fit\$3 with value\$1) and (linear\$3 with regression\$3) and (coefficient\$1 near (relat\$3 correlat\$3)) and (resist\$3 with measur\$3) and (effect\$3 with (length\$1 width))	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:12
S38	1	(monitor\$3 with (process\$3 near stability)) and (fit\$3 with value\$1) and (linear\$3 with regression\$3) and (coefficient\$1 near (relat\$3 correlat\$3)) and (resist\$3 with measur\$3) and ((effect\$3 with (length\$1 width)) same wafer\$1)	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:12
S39	0	((monitor\$3 with (process\$3 near stability)) and (fit\$3 with value\$1) and (linear\$3 with regression\$3) and (coefficient\$1 near (relat\$3 correlat\$3)) and (resist\$3 with measur\$3) and ((effect\$3 with (length\$1 width)) same wafer\$1)).clm.	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:13
S40	0	(S3 S4 S6 S7) and S38	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:13
S41	0	(S3 S4 S6 S7) and S39	US- PGPUB; USPAT; USOCR	OR	ON	2008/07/04 16:13
S42	3309	(702/57,58,109-110,117,179).CCLS.	US- PGPUB; USPAT; USOCR	OR	OFF	2008/11/18 14:05
S43	439	(324/716,718).CCLS.	US- PGPUB; USPAT; USOCR	OR	OFF	2008/11/18 14:05

S44	2814	((438/14).CCLS.	US- PGPUB; USPAT; USOCR	OR	OFF	2008/11/18 14:05
S45	6	((histo\$3 with value\$1) same curve\$1) and ((goodness with fit\$3) and ((control\$3 with limit \$3) (threshold with value\$1) (referenc\$3 with value\$1)))	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 16:15
S46	1	((test\$3 with condition\$3 with (temperatur\$3 with intensity)) and (semiconductor\$1 with structure \$1) and (resist\$3 with value\$1 with measur\$3) and (effect\$3 with (length\$1 and width\$1)) and ((divid\$3 division) with (length\$1 with width\$1)))	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 16:16
S47	1	((structure with test\$3 with parameter\$1) and ((measur\$3 with monitor\$3) with value\$1) and ((goodness with fit\$3 with differenc\$3) and (value \$1 with differenc\$3)))	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 16:17
S48	12	((wafer\$1 near defect\$1)with (screen\$3 monitor \$3)) and (statistic\$3 with process\$3 with control \$3)	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 16:26
S49	98	((wafer\$1 near defect\$1)with (screen\$3 monitor \$3)) and (process\$3 with control\$3)	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 16:26
S50	2	((wafer\$1 near defect\$1)with (screen\$3 monitor \$3)) and (statistic\$3 with process\$3 with control \$3) and (effect\$3 with (length\$1 and width\$1))	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 16:26

S51	0	((wafer\$1 near defect\$1)with (screen\$3 monitor\$3) and (statistic\$3 with process\$3 with control\$3) and (effect\$3 with (length\$1 and width\$1)) and ((effective near length\$1) with (great\$3 larg\$3) with (effect\$3 near width\$1)))	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 16:45
S52	0	S50 and S47	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 16:45
S53	0	((wafer\$1 near defect\$1)with (screen\$3 monitor\$3) and (statistic\$3 with process\$3 with control\$3) and (effect\$3 with (length\$1 and width\$1)) and ((effective near length\$1) with (great\$3 larg\$3) with (effect\$3 near width\$1))). clm.	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 16:45
S54	0	S53 and (S42 S43 S44)	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 17:12
S55	0	S51 and (S42 S43 S44)	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 17:14
S56	48	(curve near fit\$3) and (process\$3 with (control\$3 monitor\$3)) and (detect\$3 with defect\$1) and ((goodness nearl (fit\$4 measur\$3)) (coefficient\$1 near correlation\$1)) and (sheet\$1 near (resistance resistivity))	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 17:14

S57	1	(curve near fitt\$3) and (process\$3 with (control \$3 monitor\$3)) and (detect\$3 with defect\$1) and ((goodness near! (fit\$4 measur\$3)) (coefficient\$1 near correlation\$1)) and (sheet\$1 near (resistance resistivity)) and ((effectiv\$3 with (length\$1 and width\$1)) same (divis\$3 divid \$3))	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 17:15
S58	0	((curve near fitt\$3) and (process\$3 with (control \$3 monitor\$3)) and (detect\$3 with defect\$1) and ((goodness near! (fit\$4 measur\$3)) (coefficient\$1 near correlation\$1)) and (sheet\$1 near (resistance resistivity)) and ((effectiv\$3 with (length\$1 and width\$1)) same (divis\$3 divid \$3))).clm.	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 17:15
S59	0	S58 and (S42 S43 S44)	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 17:16
S60	1	S57 and (S42 S43 S44)	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 17:16
S62	3351	(702/180,182,188).CCLS.	US- PGPUB; USPAT; USOCR	OR	OFF	2008/11/18 18:07

S63	0	((curve near fit\$3) and (process\$3 with (control\$3 monitor\$3)) and (detect\$3 with defect\$1) and ((goodness near (fit\$4 measur\$3)) (coefficient\$1 near correlation\$1)) and (sheet\$1 near (resistance resistivity)) and ((effectiv\$3 with (length\$1 and width\$1)) same (divis\$3 divid\$3))).clm.	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 18:07
S64	1	(monitor\$3 with (process\$3 near stability)) and (fit\$3 with value\$1) and (linear\$3 with regression\$3) and (coefficient\$1 near (relat\$3 correlat\$3)) and (resist\$3 with measur\$3) and ((effect\$3 with (length\$1 width)) same wafer\$1)	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 18:07
S65	0	S62 and S63	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 18:07
S66	0	S62 and S64	US- PGPUB; USPAT; USOCR	OR	ON	2008/11/18 18:07

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